



## **Hoya Selects Applied Materials' Tetra Mask Etcher for 65nm Production**

June 5, 2006

SANTA CLARA, Calif.--(BUSINESS WIRE)--June 5, 2006--Applied Materials, Inc. today announced that its Applied Tetra(TM) II Mask Etch system has won the selection for 65nm mask applications at Hoya Corporation, the world's largest supplier of photomasks used in semiconductor and LCD (liquid crystal display) production. Outstanding production capabilities in advanced binary mask and phase shift mask (PSM) applications distinguishes the Tetra II Mask Etch system as the industry's tool of choice for 65nm-generation mask production worldwide. The tool is scheduled for installation at Hoya in mid-2006, in the company's Hachioji, Japan, facility.

Asao Shikata, Chief General Manager, Mask Division of Hoya said, "The Applied Tetra II system's exceptional 65nm mask etch capabilities, especially its chrome and quartz etch performance on the latest binary and phase shift mask applications, were key reasons for our purchase of this system. This system will help Hoya continue to provide the industry's most advanced masks over the next several generations of photomask technology."

The Applied Tetra II Mask Etch system offers high-productivity processes for both chrome and dielectric mask etching. For chrome etching, the system provides exceptional critical dimension control and process uniformity for all mask technologies. Its dielectric etch capabilities enable the most advanced phase-shift masks, offering mask makers the flexibility to manufacture both resist-masked as well as chrome-masked applications at high yields. The Tetra II is the only mask etch tool that can be configured with up to four mask etch chambers for maximum productivity across all commonly used applications.

"We are very pleased by Hoya's choice of Applied Materials to supply its critical enabling mask etch technology as it moves to 65nm-generation photomask manufacturing," said Tom St. Dennis, senior vice president and general manager of Applied Materials' Etch, Cleans and Front End Products Group. "The Tetra II system is being used by the majority of 65nm-generation mask makers worldwide. Its best-of-class process technology also enables customers to easily create high precision, highly uniform mask patterns with the most advanced resolution enhancement techniques."

Applied Materials, Inc. (Nasdaq:AMAT) is the global leader in nanomanufacturing technology(TM) solutions for the electronics industry with a broad portfolio of innovative equipment, service and software products. At Applied Materials, we apply nanomanufacturing technology to improve the way people live. Learn more at [www.appliedmaterials.com](http://www.appliedmaterials.com).

CONTACT: Applied Materials, Inc.  
Betty Newboe, 408-563-0647 (editorial/media)  
Randy Bane, 408-986-7916 (financial community)

SOURCE: Applied Materials, Inc.